

AMENDMENTS TO THE SPECIFICATION

Please amend paragraph 0019 starting at page 13, line 4 as follows:

[0019] Optionally, co-photoinitiators can be used with the photoinitiator. Examples of the co-photoinitiator include, without limitation, triethanolamine, methyldiethanolamine, triisopropanolamine, 4,4'-dimethylamino benzophenone, 4,4'-diethylamino benzophenone, 2-dimethylamino ethylbenzoate, 4-dimethylamino ethylbenzoate, ~~2-n-butoxyethyl-4-dimethylaminobenzoate~~ 2-n-butoxyethyl-4-dimethylaminobenzoate, 4-dimethylamino isoamylbenzoate, 4-dimethylamino-2-ethylhexyl benzoate and Eosin Y.

Please amend paragraph 0024 starting at page 15, line 18 as follows:

[0024] In the present invention, the surface-modified carbon nanotubes may be used in combination with other co-polymerizable monomers or oligomers containing double bonds for the purpose of improving the evenness of the coating film and further providing particular functionality of the monomers or oligomers. Preferable examples of the co-polymerizable monomer include, without limitation, methyl methacrylate, allyl acrylate, benzyl acrylate, butoxyethyl acrylate, 2-cyanoethyl acrylate, cyclohexyl acrylate, dicyclopentenyl acrylate, N,N-diethylaminoethyl acrylate, 2-ethoxyethyl

acrylate, 2-ethylhexyl acrylate, glycerol methacrylate, glycidyl methacrylate, heptadecafluorodecyl acrylate, 2-hydroxyethyl acrylate, 2-hydroxy-3-methacryloxypropyl trimethyl ~~ammonium~~ ammonium chloride, 2-hydroxypropyl acrylate, isobornyl acrylate, isodecyl acrylate, isooctyl acrylate, lauryl acrylate, 2-methoxyethyl acrylate, methoxytriethyleneglycol acrylate, nonylphenoxy polyethyleneglycol acrylate, octafluoropentyl acrylate, phenoxyhydroxypropyl acrylate, phenoxy methacrylate, phosphoric acid methacrylate, phthalic acid acrylate, polyethyleneglycol methacrylate, stearyl acrylate, tetrafluoropropyl acrylate, trifluoroethyl acrylate, vinyl acetate, N-vinyl caprolactam, N-vinyl-2-pyrrolidone and ~~acryl-amide~~ acrylamide. Preferable examples of the co-polymerizable oligomer include, without limitation, epoxy acrylate, urethane acrylate and polybutadiene acrylate. Such co-polymerizable monomers or oligomers are added to the liquid coating composition comprising the surface-modified carbon nanotubes with a weigh ratio of carbon nanotube to monomer or oligomer (i.e. weight of carbon nanotube : weight of monomer or oligomer) ranging from 5:95 to 99:1, preferably 10:90 ~ 95:5.

Please amend paragraph 0032 starting at page 21, line 9 as follows:

[0032] After stirring for 1hr for mixing the ingredients, the liquid coating composition was applied onto a ~~silicone~~ silicon wafer by spin coating at 500rpm, followed by drying at 100°C for 1 minute to evaporate solvent. The resulting coating film was masked with a photomask of a desired pattern and

then exposed to UV light at an exposure dose of 500mJ/cm². Subsequently, the exposed film was developed with DMF for 20 seconds to afford a negative pattern of acrylated carbon nanotubes.

Please amend paragraph 0034 starting at page 22, line 10 as follows:

[0034] After stirring for 1hr for mixing the ingredients, the liquid coating composition was applied onto a ~~silicone~~ silicon wafer by spin coating at 500rpm, followed by drying at 100°C for 1 minute to evaporate solvent. The resulting coating film was masked with a photomask of a desired pattern and then exposed to UV light at an exposure dose of 350 mJ/cm². Subsequently, the exposed film was developed with DMF for 20 seconds to afford a negative pattern of acrylated carbon nanotubes.

Please amend paragraph 0036 starting at page 23, line 10 as follows:

[0036] After stirring for 1hr for mixing the ingredients, the liquid coating composition was applied onto a ~~silicone~~ silicon wafer by spin coating at 500rpm, followed by drying at 100°C for 1 minute to evaporate solvent. The resulting coating film was masked with a photomask of a desired pattern and then exposed to UV light at an exposure dose of 400mJ/cm². Subsequently, the exposed film was developed with DMF for 20 seconds to afford a negative pattern of vinylbenzylated carbon nanotubes.

Please amend paragraph 0038 starting at page 24, line 12 as follows:

[0038] After stirring for 1hr for mixing the ingredients, the liquid coating composition was applied onto a ~~silicone~~ silicon wafer by spin coating at 800rpm, followed by drying at 100°C for 1 minute to evaporate solvent. The resulting coating film was masked with a photomask of a desired pattern and then exposed to UV light at an exposure dose of 600mJ/cm². Subsequently, the exposed film was developed with DMF for 30 seconds to afford a negative pattern of acrylated carbon nanotubes.

Please amend paragraph 0040 starting at page 25, line 11 as follows:

[0040] After stirring for 1hr for mixing the ingredients, the liquid coating composition was applied onto a ~~silicone~~ silicon wafer by spin coating at 800rpm, followed by drying at 100°C for 1 minute to evaporate solvent. The resulting coating film was masked with a photomask of a desired pattern and then exposed to UV light at an exposure dose of 600mJ/cm². Subsequently, the exposed film was developed with DMF for 30 seconds to afford a negative pattern of acrylated carbon nanotubes.